

Form PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
MI22-1896SERIAL NO.
09/633,556LIST OF ART CITED BY APPLICANT
(Use several sheets if necessary)APPLICANT
Gurtej S. Sandhu et al.FILING DATE
August 7, 2000GROUP
2813

U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
<i>[Signature]</i>	AA	5,032,545	07/91	Doan et al.			
<i>[Signature]</i>	AB	5,436,481	07/95	Egawa et al.			
<i>[Signature]</i>	AC	5,378,645	01/95	Inoue et al.			
<i>[Signature]</i>	AD	5,258,333	11/93	Shappir et al.			
<i>[Signature]</i>	AE	5,518,946	05/96	Kuroda			
<i>[Signature]</i>	AF	5,445,999	08/95	Thakur et al.			
<i>[Signature]</i>	AG	5,382,533	01/95	Ahmad et al.			
<i>[Signature]</i>	AH	5,663,077	09/97	Adachi et al.			
<i>[Signature]</i>	AI	5,026,574	06/91	Economu et al.			
<i>[Signature]</i>	AJ	5,026,574	06/91	Economu et al.			
<i>[Signature]</i>	AK	5,612,558	3/1997 11/95	Harshfield			
<i>[Signature]</i>	AL	5,719,083	2/1998 06/95	Komatsu			

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		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AM	WO 96/39713	12/96	PCT				
	AN							
	AO							
	AP							
	AQ							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

<i>[Signature]</i>	AR		Wolf, S., "Silicon Processing for the VLSI Era", Lattice Press 1990, Vol. 2, pp. 212-213.
<i>[Signature]</i>	AS		Wolf, S., "Silicon Processing for the VLSI Era", Lattice Press 1990, Vol. 2, pp. 188-189, 194-195, 609-614.
	AT		Ko, L. et al., "The Effect of Nitrogen Incorporation into the Gate Oxide By Using Shallow Implantation of Nitrogen and Drive-In Process", IEEE 1996, pp. 32-35.

EXAMINER

DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
AA	5,760,475	06/98	Cronin				
AB	5,834,372	11/98	Lee				
AC	5,619,057	04/98	Komatsu				
AD	5,633,036	05/97	Seebauer et al.				
AE	6,054,396	04/00	Doan				
AF	6,174,821	01/01	Doan				
AG	5,939,750	08/99	Early				
AH	5,254,489	10/93	Nakata				
AI	5,464,792	11/95	Tseng et al.				
AJ	5,620,908	04/97	Inoh et al.				
AK	5,716,864	02/98	Abe				
AL	5,972,783	10/99	Arai et al.				
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AR		Doyle, B. et al., "Simultaneous Growth of Different Thickness Gate Oxides in Silicon CMOS Processing", IEEE Vol. 16 (7), July 1995, pp. 301-302.					
AS		Kuroi, T. et al., "The Effects of Nitrogen Implantation Into P+Poly-Silicon Gate on Gate Oxide Properties", 1994 Sympos. on VLSI Technology Digest of Technical Papers, IEEE 1994, pp. 107-108.					
AT		Liu, C.T. et al., "Multiple Gate Oxide Thickness for 2GHz System-on-a-Chip Technologies", IEEE 1998, pp. 589-592.					
EXAMINER <i>Wanda Schultz</i>				DATE CONSIDERED <i>9/30/02</i>			
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<i>JS</i>	AA	6,091,109	07/00	Hasegawa				
<i>JS</i>	AB	6,080,682	06/00	Ibok				
<i>JS</i>	AC	5,685,949	11/97	Yashima				
<i>JS</i>	AD	6,268,296 B1	07/01	Misium et al.				
<i>JS</i>	AE	6,232,244 B1	05/01	Ibok				
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	AG							
	AH							
	AI							
	AJ							
	AK							
	AL							
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